

REMARKS

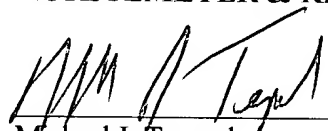
It is hereby respectfully requested that the Examiner enter the Amendment to the above-referenced divisional patent application. Should there be any questions or comments concerning the amendments or remarks referenced herein, the Examiner is respectfully requested to contact the undersigned attorney.

Respectfully submitted,

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By:



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**ANNOTATED VERSION OF MODIFIED SPECIFICATION TO SHOW CHANGES
MADE**

In The Specification

Page 1, line 6, delete "document" and substitute therefor:

--application is a division of U.S. Application Serial No. 08/932,025, entitled 'Method
And Apparatus For Low Energy Electron Enhanced Etching of Substrates in an AC or DC
Plasma Environment, filed September 17, 1997, which--.